## Supporting information

## Phosphorene nano-heterostructure based memristor with broadband response synaptic plasticity

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Figure S1. The typical EDS spectra of single ZP NP. The inset chart shows the atomic ratio of each element.



**Figure S2.** The type-II staggered band configuration of ZnO NPs and phosphorene (BP) QDs.



**Figure S3.** (a-c) I-V characteristics of the device showing gradual conductance enhancement by applying 4 consecutive positive sweeps after illumination with wavelength of 633 nm (a), 532 nm (b) and 380 nm (c). (d-f) I-V characteristics of the device showing gradual conductance depression by applying 4 consecutive negative sweeps after illumination with wavelength of 633 nm (d), 532 nm (e) and 380 nm (f).



**Figure S4.** Potential change (a) after UV light illumination and (b) its dependence on the vertical distance recorded after 5, 10, 15 and 20 min.



**Figure S5.** (a) Band alignment of device at initial state. (b-d) Illustration of device structure at the initial state (b), conduction filament forming process in the dark condition (c), and conduction filament forming under the illumination (d).



**Figure S6.** The exponential fitting data of EPSC in dark condition.  $I_0$ , A and  $\tau$  corresponds to 7.81E-7 A, 1E-4 and 0.21 s, respectively.



**Figure S7.** PPF (a) before and after illuminations with wavelength of (b) 633 nm, (c) 532 nm and (d) 380 nm by applying negative pulse trains.



**Figure S8.** Conductance change of synaptic devices under 10 consecutive pulse trains with the base value of 1 V for 0.1 s and pulse amplitude of 5 V for 0.1 s. Different molar ratio of ZnO to phosphorene ranges from 7: 1 to 9: 1.



Figure S9. Conductance depression by consecutive 40 pulse trains in negative directions.



**Figure S10.** Pre- and post-synaptic spikes utilized to implement Symmetric Hebbian rule and Symmetric anti-Hebbian rule.

	Interval 0.1s			In	Interval 0.01s		
N cycles	lo	A	τ	lo	A	τ	
10	7.42E-7	1.83E-6	16.82	1.51E-6	9.05E-6	7.55	
20	8.75E-7	2.21E-6	17.25	1.63E-6	1.11E-5	8.04	
30	1.16E-6	4.37E-6	17.18	2.00E-6	1.17E-5	18.99	
40	2.50E-6	1.53E-5	19.00	3.29E-6	1.19E-5	25.06	
50	3.08E-6	1.54E-5	20.18	7.36E-6	1.31E-5	40.30	
60	4.95E-6	2.39E-5	20.88	9.12E-6	1.41E-5	50.32	

**Table S1.** Fitting results for Figure 4b-c.